

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|--|---|---------------------|
| 17 | 3923 | ((photosensitive or (resist near4 film\$1)) and (mask\$4 or pattern\$1) and (substrate\$1 or workpiece\$1) and ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/16 12:54 |
| 18 | 306 | ((photosensitive or (resist near4 film\$1)) and (mask\$4 or pattern\$1) and (substrate\$1 or workpiece\$1) and ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) and ((photosensitive or (resist near4 film\$1)) same (mask\$4 or pattern\$1) same ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/16 13:01 |
| 20 | 42 | ((photosensitive or (resist near4 film\$1)) and (mask\$4 or pattern\$1) and (substrate\$1 or workpiece\$1) and ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) and ((photosensitive or (resist near4 film\$1)) same (mask\$4 or pattern\$1) same ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) and (347/\$.ccls.) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/16 13:01 |
| 27 | 25 | ((photosensitive or (resist near4 film\$1)) and (mask\$4 or pattern\$1) and (substrate\$1 or workpiece\$1) and ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) and ((photosensitive or (resist near4 film\$1)) same (mask\$4 or pattern\$1) same ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) and (347/\$.ccls.) and align\$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/16 13:01 |
| 28 | 13 | ((photosensitive or (resist near4 film\$1)) and (mask\$4 or pattern\$1) and (substrate\$1 or workpiece\$1) and ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) and ((photosensitive or (resist near4 film\$1)) same (mask\$4 or pattern\$1) same ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) and (347/\$.ccls.) and align\$4 and mov\$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/16 13:03 |
| 29 | 8 | ((photosensitive or (resist near4 film\$1)) and (mask\$4 or pattern\$1) and (substrate\$1 or workpiece\$1) and ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) and ((photosensitive or (resist near4 film\$1)) same (mask\$4 or pattern\$1) same ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1))) and (347/\$.ccls.) and align\$4 and mov\$4 and rotat\$4 | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/01/16 13:02 |

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|----|----|--|---|-----------------------------|
| 30 | 34 | <p>(((photosensitive or (resist near4 film\$1)) and (mask\$4 or pattern\$1) and (substrate\$1 or workpiece\$1) and ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1)))) and ((photosensitive or (resist near4 film\$1)) same (mask\$4 or pattern\$1) same ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1)))) and (347/\$.ccls.) not ((((((photosensitive or (resist near4 film\$1)) and (mask\$4 or pattern\$1) and (substrate\$1 or workpiece\$1) and ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1)))) and ((photosensitive or (resist near4 film\$1)) same (mask\$4 or pattern\$1) same ((deposit\$4 or eject\$4) with (ink\$1 or liquid\$1 or fluid\$1)))) and (347/\$.ccls.)) and align\$4) and mov\$4) and rotat\$4)</p> | <p>USPAT; US-PGPUB; EPO; JPO; DERWENT</p> | <p>2004/01/16 13:03</p> |
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